

METHODOLOGY FOR CRITICAL DIMENSION METROLOGY

USING STEPPER FOCUS MONITOR INFORMATION

ABSTRACT

A method of producing an accurate critical dimension measurement comprises navigating
5 to a critical dimension structure, performing a scanning electron microscope focusing,
performing a final location alignment, acquiring waveform data, analyzing the data to determine
an approximate critical dimension, analyzing the data to determine a stepper focus parameter,
combining the stepper focus parameter with the critical dimension to generate an accurate critical
dimension value, and reporting the same.